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J. Micro/Nanolith. MEMS MOEMS. 2012;11(2):021105-1-021105-10. doi:10.1117/1.JMM.11.2.021105

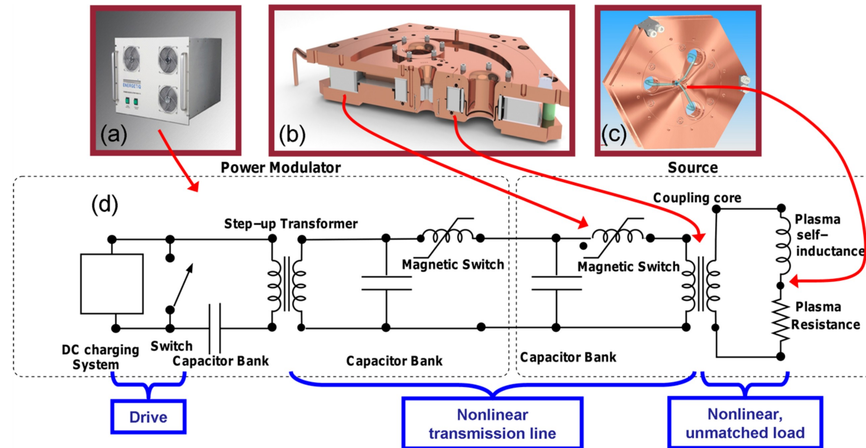

Figure Legend:

Illustrations (a)–(c) and schematic (d) demonstrating the key structures of the Xenon electrodeless Z-pinch extreme ultraviolet (EUV) light source.

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